

S/N UnknownPATENTIN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant: Stephen Y. Chou  
Serial No.: Unknown  
Filed: Herewith  
Title: IMPROVED RELEASE SURFACES, PARTICULARLY FOR USE IN NANOIMPRINT LITHOGRAPHY

Examiner: Unknown  
Group Art Unit: Unknown  
Docket: 600.426US2

INFORMATION DISCLOSURE STATEMENT

Box Patent Application  
Commissioner for Patents  
Washington, D.C. 20231

In compliance with the duty imposed by 37 C.F.R. § 1.56, and in accordance with 37 C.F.R. §§ 1.97 *et. seq.*, the enclosed materials are brought to the attention of the Examiner for review in connection with the above-identified patent application. Pursuant to the provisions of MPEP 609, Applicant requests that a copy of the 1449 form, initialed as being considered by the Examiner be returned to the Applicant.

In accordance with 37 C.F.R. §1.98(d), copies of the listed documents are not provided as these references were previously cited by or submitted to the U.S. Patent Office in connection with Applicant's prior U.S. application, Serial No. 09/107,006, filed on June 30, 1998, which is relied upon for an earlier filing date under 35 U.S.C. §120.

Applicant respectfully request consideration of these references during prosecution of the above-identified matter. The Examiner is invited to contact the Applicant's Representative at the below-listed telephone number if there are any questions regarding this communication.

Respectfully submitted,

STEPHEN Y. CHOU

By his Representatives,

SCHWEGMAN, LUNDBERG, WOESSNER & KLUTH, P.A.  
P.O. Box 2938  
Minneapolis, MN 55402  
(612) 359-3261

Date 10/28/01

By 

Gary J. Speier  
Reg. No. 45,458

"Express Mail" mailing label number: EL873861011US  
Date of Deposit: October 29, 2001

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Form 1449*	Atty. Docket No.: 600.426US2	Serial No. Unknown
INFORMATION DISCLOSURE STATEMENT BY APPLICANT (Use several sheets if necessary)	Applicant: Stephen Y. Chou	
	Filing Date: Herewith	Group: Unknown

## U.S. PATENT DOCUMENTS

**Examiner Initial	Document Number	Date	Name	Class	Subclass	Filing Date if Appropriate
	3,743,842	07/03/1973	Smith, H.I., et al.	250	320	01/14/72
	4,310,743	01/12/1982	Seliger, R.L.	219	121 EB	09/24/79
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## FOREIGN PATENT DOCUMENTS

**Examiner Initial	Document Number	Date	Country	Class	Subclass	Translation Yes   No
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## OTHER DOCUMENTS

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**Examiner Initial	
	Broere, et al., "250-A Linewidths with PMMA Electron Resist", <u>Applied Physics Letter 33 (5)</u> , 1978 American Institute of Physics, 392-394, (September 1, 1978)
	Chou, S.Y., et al., "Imprint Lithography with 25-Nanometer Resolution", <u>Science, Vol 272</u> , 85-87, (April 5, 1996)
	Early, K., et al., "Absence of Resolution Degradation in X-Ray Lithography for Wavelength from 4.5nm to 0.83nm", <u>Microelectronic Engineering 11</u> , Elsevier Science Publishers B.V., 317-321, (1990)
	Fischer, et al., "10 nm Electron Beam Lithography and sub-50 nm Overlay Using a Modified Scanning Electron Microscope", <u>Applied Physics Letter 62 (23)</u> , 1993 American Institute of Physics, 2989-2991, (June 7, 1993)

Examiner

Date Considered

\*Substitute Disclosure Statement Form (PTO-1449)

--EXAMINER: Initial if citation considered, whether or not citation is in conformance with WEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

Sheet 2 of \*P\*

Form 1449*	Atty. Docket No.: 600.426US2	Serial No. Unknown
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## OTHER DOCUMENTS

(Including Author, Title, Date, Pertinent Pages, Etc.)

\*\*Examiner  
Initial

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	Li, et al., "Molding of Plastic Components Using Micro-EDM Tools", <u>IEEE/CHMT International Electronics Manufacturing Technology Symposium</u> , 145-149, (1992)
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Examiner

Date Considered

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